

*IN THE UNITED STATES PATENT AND TRADEMARK OFFICE*

In re PATENT APPLICATION of :

Takeshi MORITA :

Serial No. [NEW] :

Filed: July 28, 2003 :

Method for Estimating Remaining Film Thickness Distribution, Method for Designing Patterning Mask Using the Method for Estimating Remaining Film Thickness Distribution, and Method for Manufacturing Semiconductor Devices by Using Patterning Mask Designed by Using the Method for Estimating Remaining Film Thickness Distribution

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**PRELIMINARY AMENDMENT**

U.S. Patent and Trademark Office  
2011 South Clark Place  
Customer Window, **Mail Stop Patent Application**  
Crystal Plaza Two, Lobby, Room 1B03  
Arlington, VA 22202

Sir:

Preliminary to the examination of the above-identified application,  
please amend the above-identified application as follows:

**Amendments to the Claims** are reflected in the listing of claims which  
begins of page 2 of this paper.

**Remarks** begin on page 7 of this paper.